

From: [Ravi Todi](#)
To: [Campbell, Joseph - 0552 - MITLL](#)
Cc: [Rothschild, Mordechai - 0800 - MITLL](#); [Laura Riello](#)
Subject: Re: IEEE Milestone for "Development of 193-nm Projection Photolithography"
Date: Wednesday, February 9, 2022 7:59:19 PM

Dear Joe,

Thank you for reaching out. development of 193nm lithography has certainly kept the semiconductor industry going and EDS would be happy to support this IEEE milestone dedication.

Regards,
Ravi

On Sun, Feb 6, 2022 at 12:06 AM Campbell, Joseph - 0552 - MITLL <jpc@ll.mit.edu> wrote:

Dear Ravi,

I am working with a team here at MIT Lincoln Laboratory on an IEEE Milestone proposal for the *Development of 193-nm Projection Photolithography*. The IEEE EDS would likely be one of the so-called IEEE Organizational Units with respect to our proposal. Do you agree?

Are you currently the IEEE EDS ExCom President?

For reference, I am also reaching out to Prof. Can Bayram, as the (former?) IEEE EDS OD TC Chair and to learn who is the current Chair. Would you happen to know?

Kind regards,

Joe

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[Joseph P. Campbell, PhD, FIEEE](#)

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